## Notice of References Cited Application/Control No. 10/817,145 Examiner Mia M. Thomas Applicant(s)/Patent Under Reexamination SCHATZ ET AL. Page 1 of 1

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	Α	US-2003/0048939	03-2003	Lehman, Yonatan	382/144
*	В	US-6,656,648	12-2003	Inoue, Hiromu	430/30
*	С	US-2004/0207836	10-2004	Chhibber et al.	. 356/237.4
*	D	US-2004/0126673	07-2004	Udagawa et al.	430/005
*	E	US-2002/0102015	08-2002	HUNATSU, HIROYUKI	382/144
	F	US-			
	G	US-			
	Н	US-			
	ı	US-			·
	J	US-			
	К	US-			
	L	US-			
	М	US-			

## FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Ρ					·
	a					
	R					
	S					
	Т	<del>.</del>				

## **NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)					
	U	Schatz, Th. et al. "Results of a round robin measurement on a new CD mask standard", 2003, Proc. 19th EMC, GMM-Fachbericht 39, 37-45					
	<b>V</b>	Liang, Ted et al. "Demonstration of Damage-Free Mask RepairUsing Electron Beam-Induced Processes", SPIE, Proc. vol. 4688, pg 375-382 (2002).					
	w						
	x						

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.